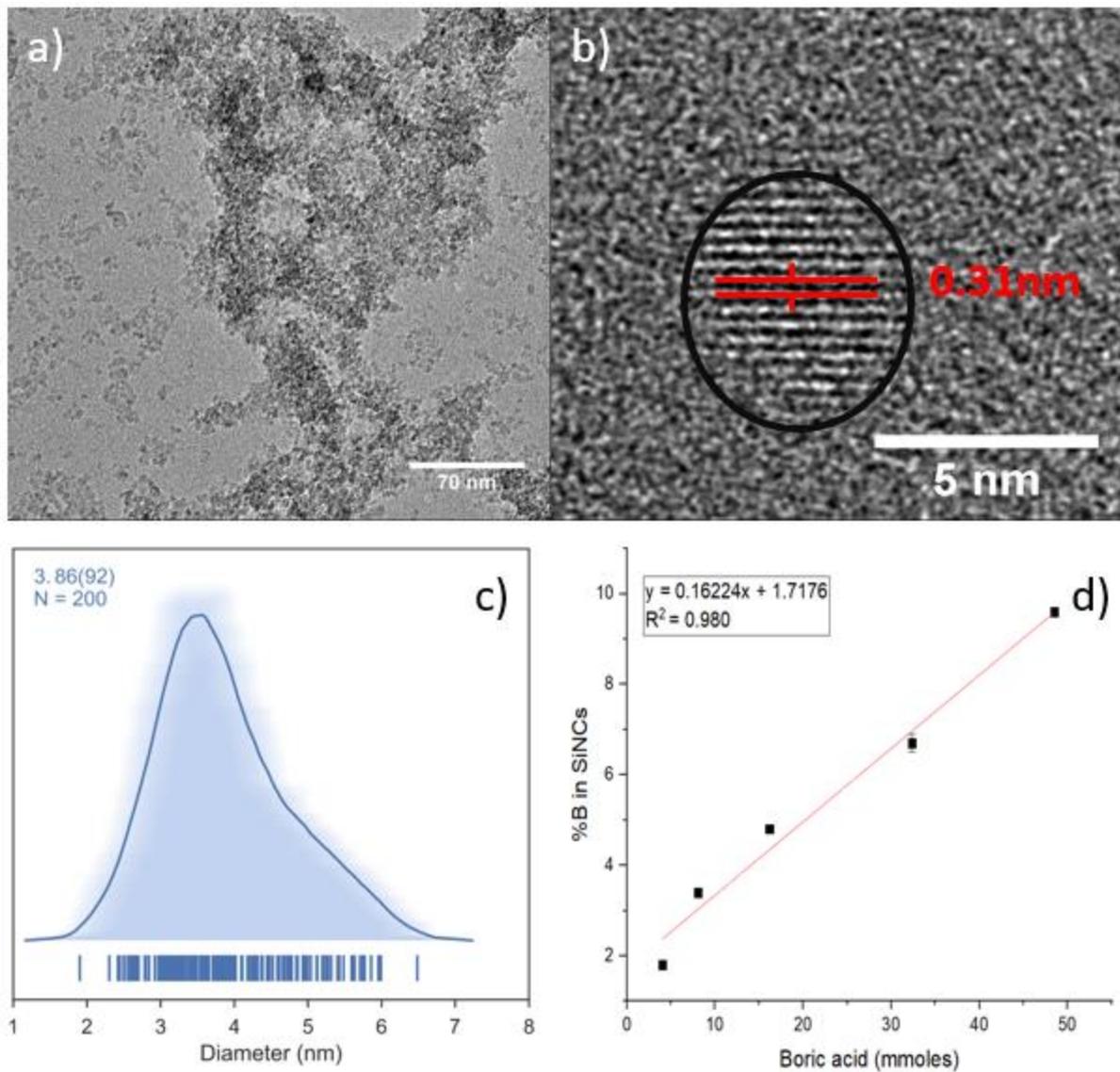


**Supporting Information for:**  
**Tailoring B-Doped Silicon Nanocrystal Surface Chemistry via Phosphorous  
Pentachloride – Mediated Surface Alkoxylation**

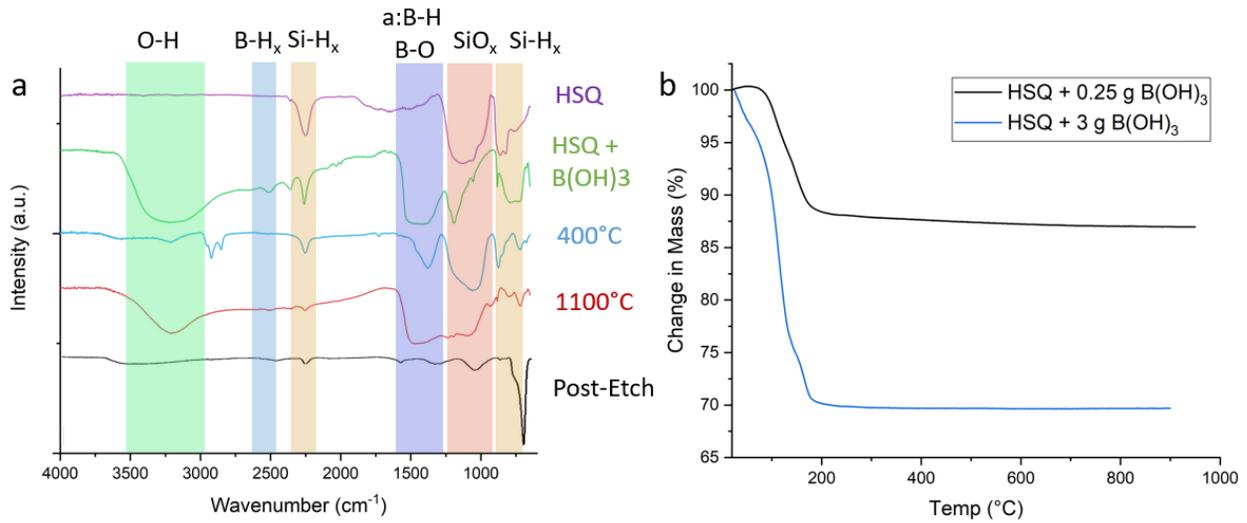
Sarah Milliken, Kai Cui, Brittney A. Klein, Haoyang Yu, Vladimir K. Michaelis, Jonathan G.C. Veinot

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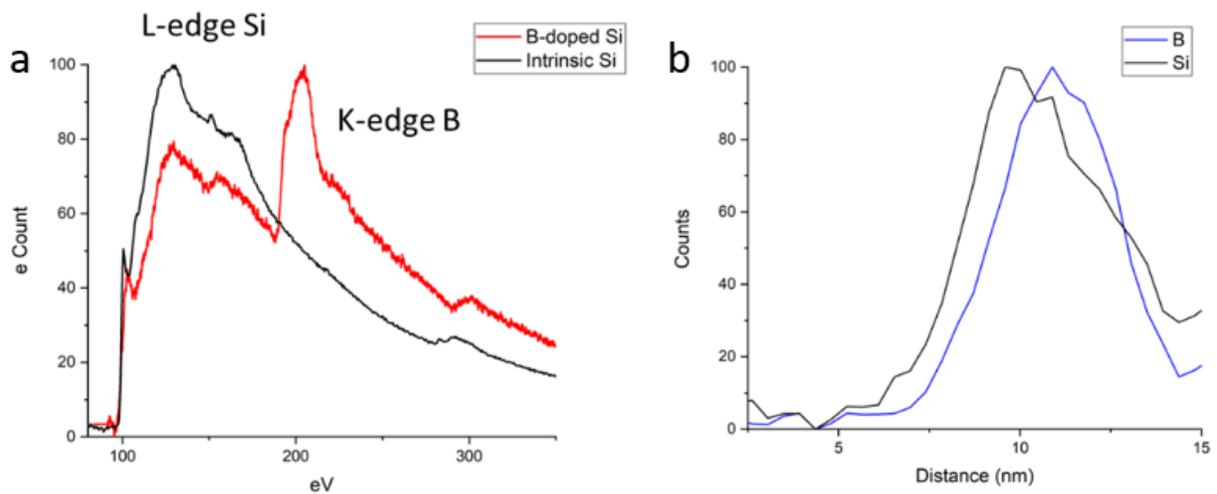
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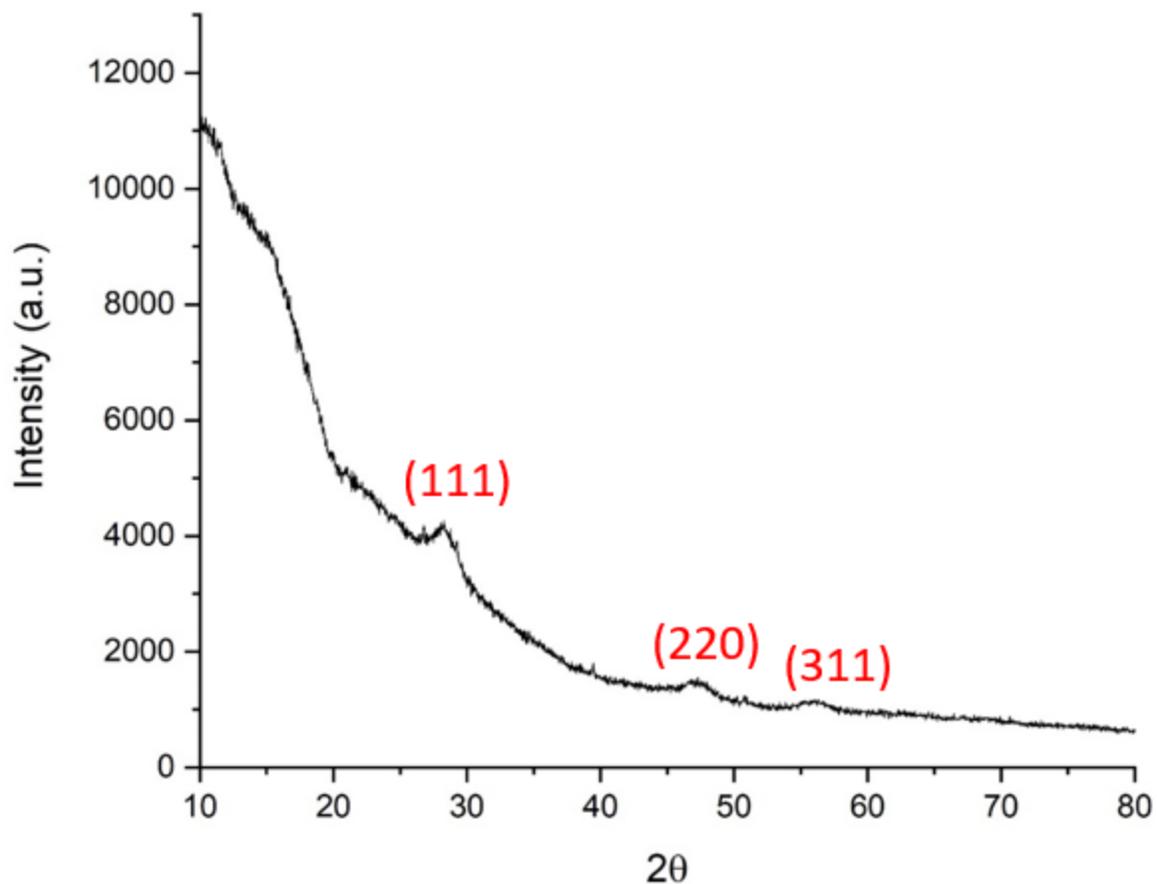
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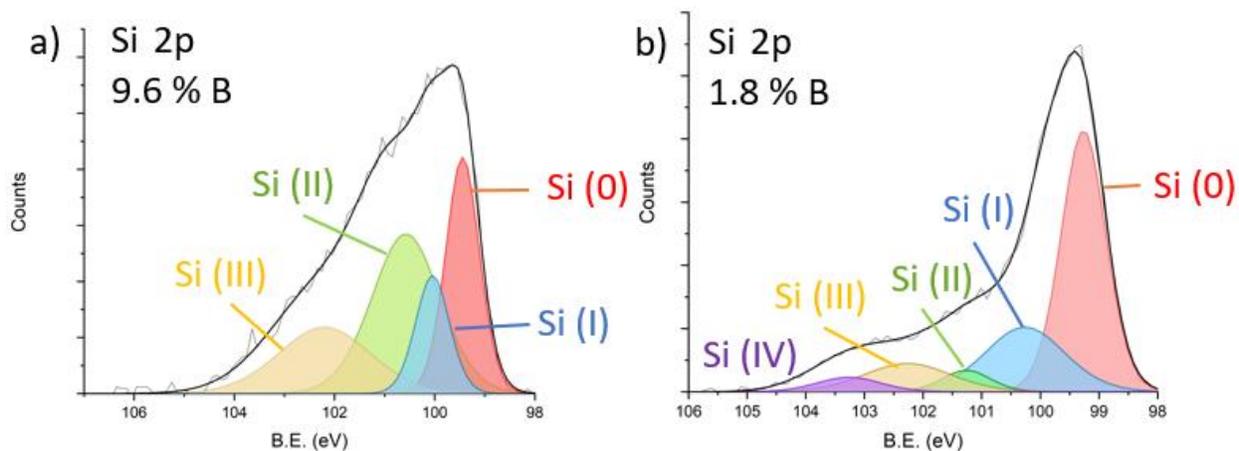
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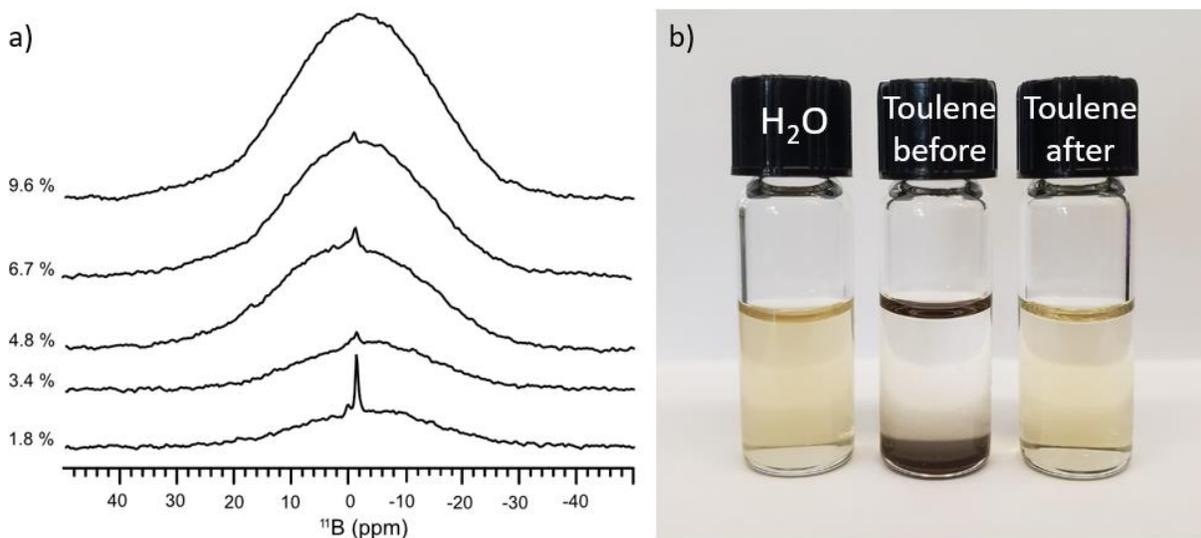
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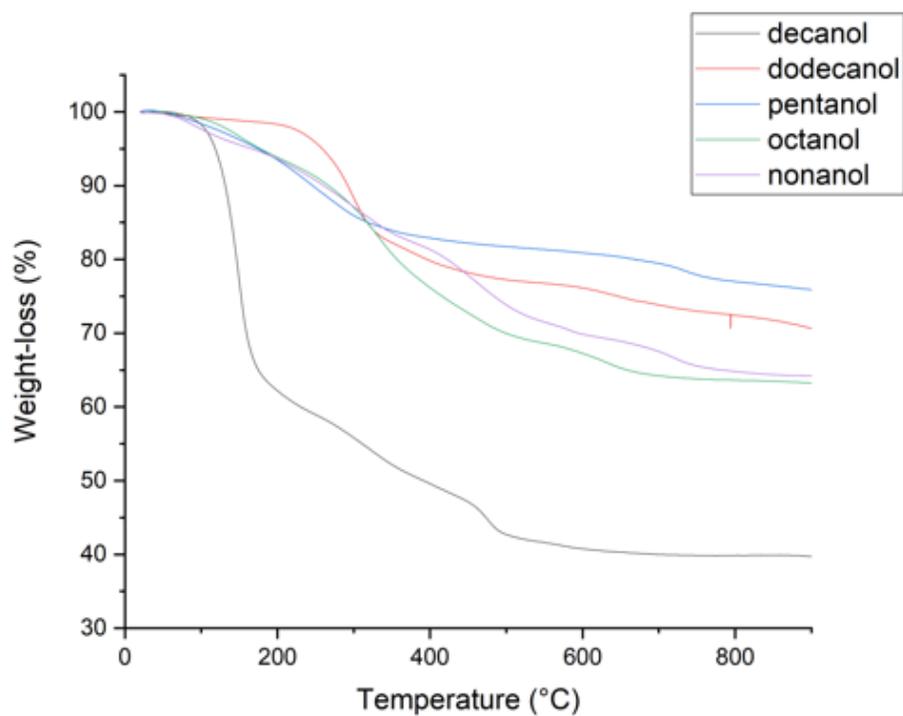
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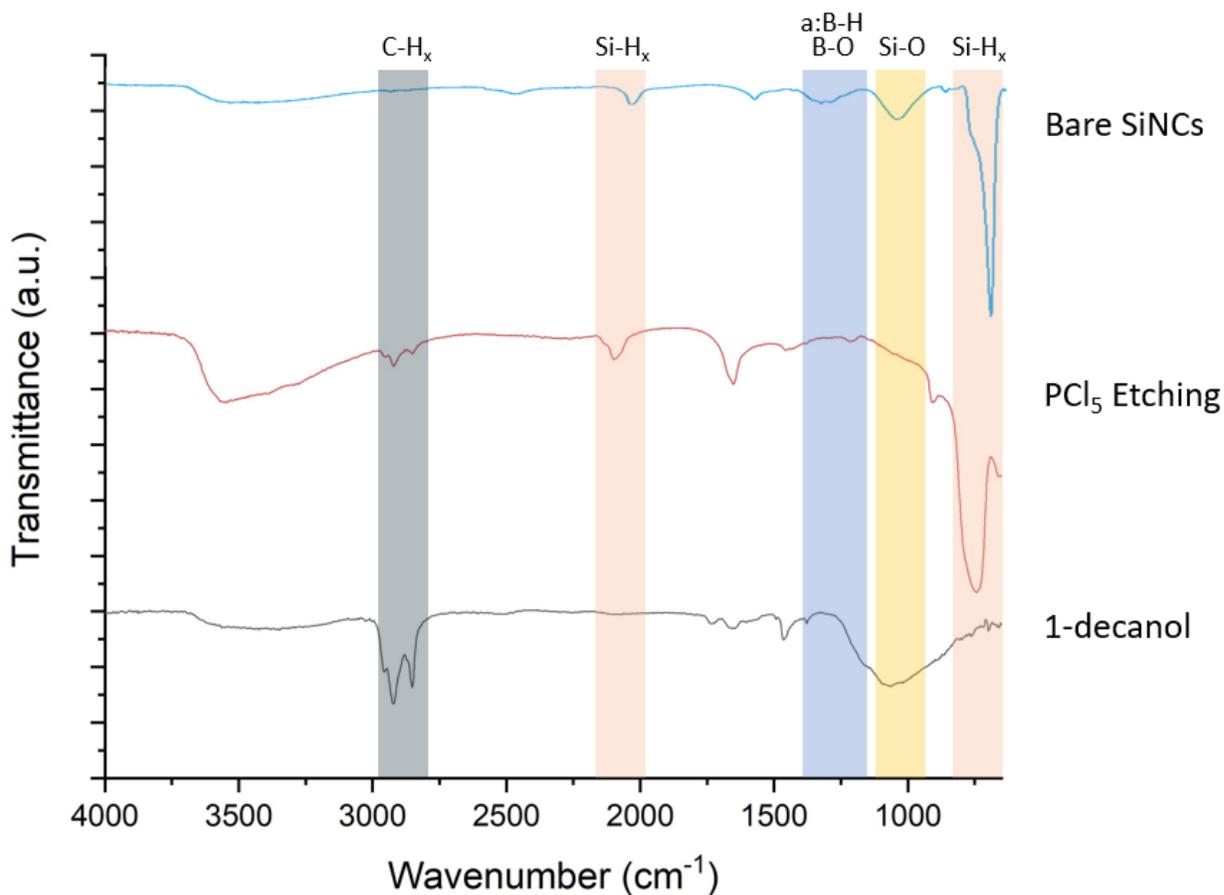
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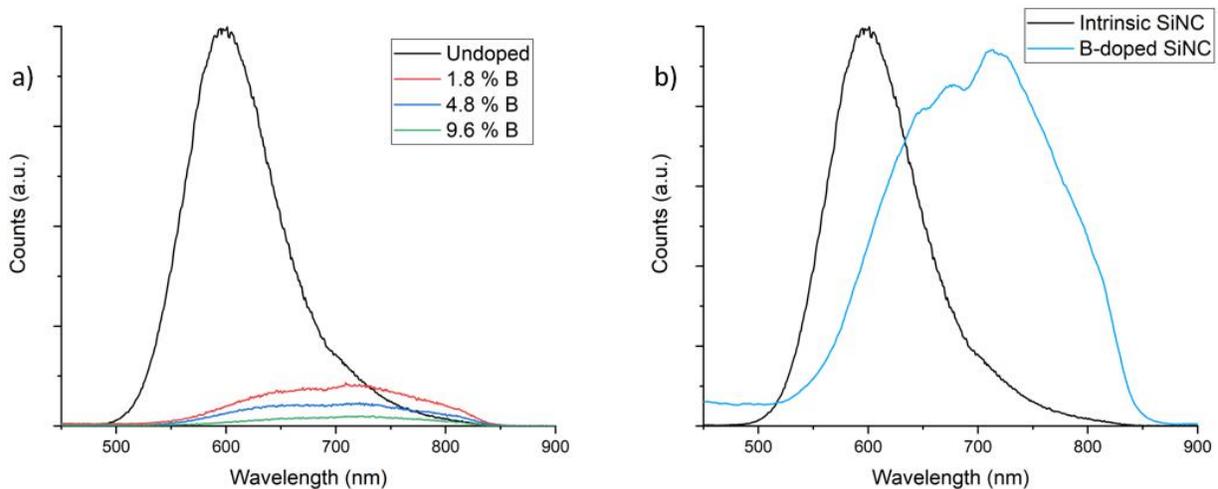
**Figure S7** TGA weight-loss plots for 9.6 atomic % B-doped SiNCs functionalized with the indicated alkoxy ligands using the  $\text{PCl}_5$ /thermal method described in Scheme 2.

**Table S1** Surface coverage of 9.6 at. % B-doped SiNCs with different ligands calculated using TGA analysis

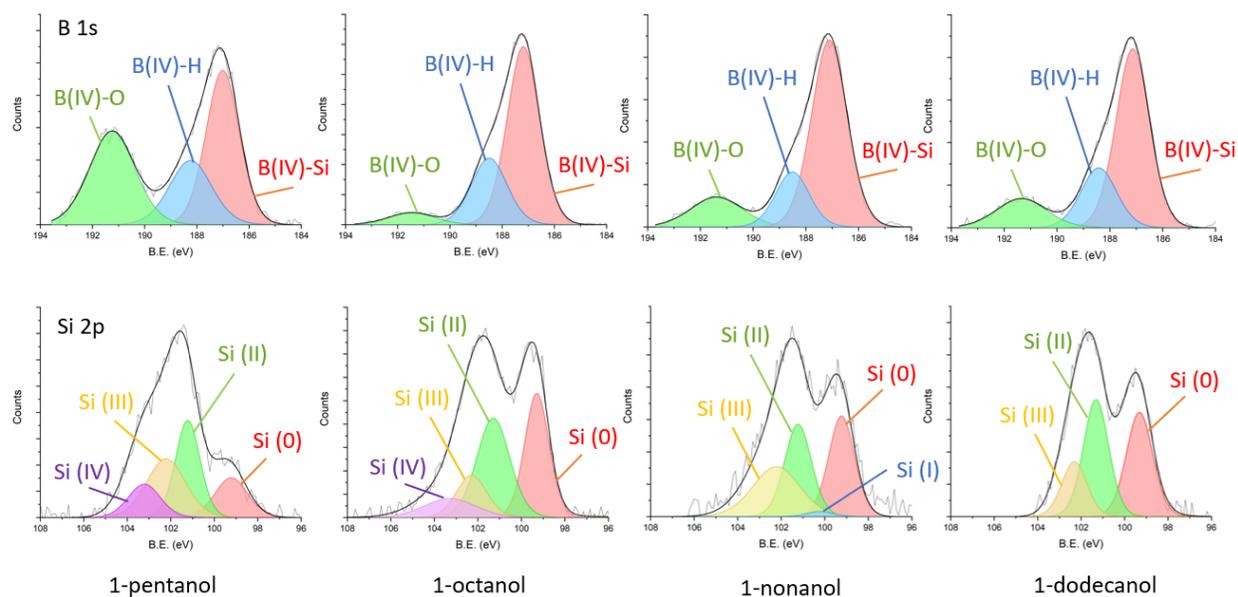
Ligand	Theoretical Weight-loss (%)	Experimental Weight-loss (%)	Surface Coverage
1-pentanol	46.27	25.15	54.35
1-octanol	55.99	41.45	74.03
1-nonanol	58.50	48.07	82.78
1-decanol	60.70	58.20	95.90
1-dodecanol	64.54	30.90	47.91



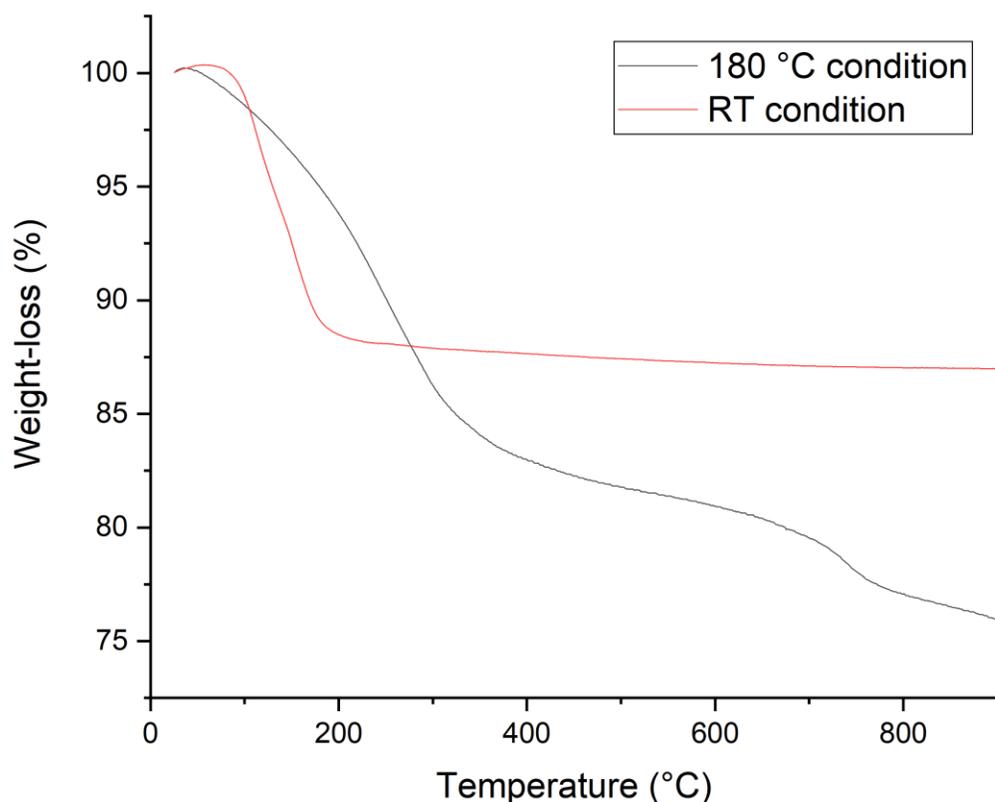
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**Table S2** Surface coverage of 9.6% B-doped SiNC with 1-pentonal with and without heating at 180 °C calculated using TGA analysis

Method	Theoretical Weight-loss (%)	Experimental Weight-loss (%)	Surface Coverage
Room temperature	46.27	13.38	28.92
Heating	46.27	25.15	54.35

Surface coverage calculation: The surface coverage from TGA weight-loss was calculated as follows:

$$\% \text{ Surface Coverage} = \frac{\% \text{ Experimental weight loss}}{\% \text{ Theoretical weight loss}} \quad (1)$$

$$\% \text{ Theoretical weight loss} = \frac{\text{Ligands theoretical weight}}{\text{Ligands and SiNCs theoretical weight}} \times 100 \quad (2)$$

$$\text{SiNCs theoretical weight} = \frac{N(\text{Si}) \times M(\text{Si})}{N_A} \quad (3)$$

$$\text{Ligands theoretical weight} = \frac{N(L) \times M(L)}{N_A} \quad (4)$$

Where  $N(\text{Si})$  = Total number of silicon atoms per nanocrystal

$N(L)$  = Total number of ligands per nanocrystal surface

$M(\text{Si})$  = Molar mass of Si

$M(L)$  = Molar mass of ligand

$N_A$  = Avogadro's number

Substituting equation (3) and (4) into equation (2) simplifying results in equation (5)

$$\% \text{Theoretical weight loss} = \frac{N(L) \cdot M(L)}{N(L) \cdot M(L) + N(\text{Si}) \cdot M(\text{Si})} \times 100 \quad (5)$$